Special Issue on

Nanofabrication, Atomic and Close-to-atomic Scale Manufacturing

Guest Editors:

- Prof. Xichun Luo, University of Strathclyde, UK; xichun.luo@strath.ac.uk
- Prof. Jiang Guo, Dalian University of Technology, P. R. China; guojiang@dlut.edu.cn
- Dr. Saeed Chavoosi, Imperial College London, UK; s.zare@imperial.ac.uk

Scope of this special issue

Papers in all areas of nanofabrication and atomic and close-to-atomic scale manufacturing (ACSM) technologies will be considered, including but not limited to:

- Lithography technologies (extreme ultraviolet, electron beam, focused ion beam, nanoimprint, etc.)
- Ultra-precision diamond turning/milling/grinding
- Ultra-precision polishing (ion/plasma/RAPT/MRF/EEM/CMP/Fluid jet, etc.)
- Ultrafast laser machining
- Directed self-assembly
- Nano 3D printing
- Atomic layer deposition
- AFM tip-based nanomachining and lithography technologies
- STM atomic manipulation
- Modelling and simulation technologies for nanofabrication and ACSM
- Test-bed/machines for nanofabrication and ACSM
- Metrology technologies/devices/instruments for nanofabrication and ACSM

Original research papers, review articles and short communications are all welcome

All manuscripts must be submitted through the manuscripts system at

https://www.editorialmanager.com/nmme/default.aspx

**Submission Deadline:** 15 June 2020

**Publication Date:** September 2020